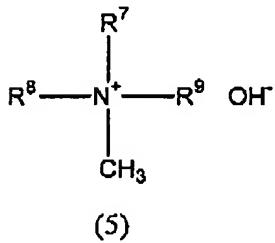
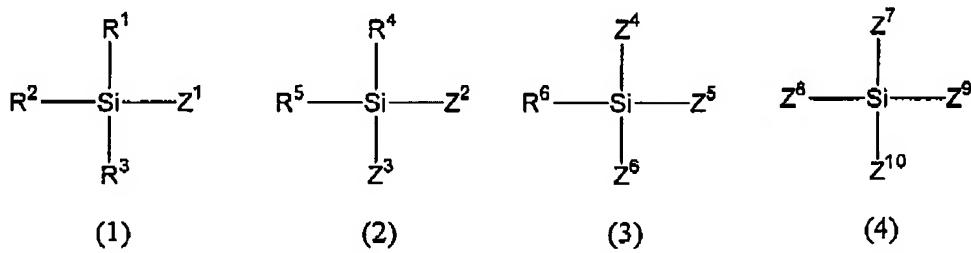


Appl. No.: 10/796,656
 Amdt. dated 07/24/2006
 Reply to Office action of March 22, 2006

Amendments to the Claims:

1. (Currently amended) A composition for forming a porous film comprising 10 ppm or less halogen impurity and 10 ppb or less metallic impurity wherein boron is counted in the metallic impurity, the composition comprising a hydrolysis and condensation product of an alkoxy silane or a partial hydrolysis product of the alkoxy silane in an organic solvent in the presence of trialkylmethylammonium hydroxide as a catalyst, wherein the alkoxy silane comprises one or more alkoxy silanes selected from the groups consisting of compounds represented by formulae (1) to (4) below, and the trialkylmethylammonium hydroxide is represented by formula (5) below,



wherein Z^1 , Z^2 , Z^3 , Z^4 , Z^5 , Z^6 , Z^7 , Z^8 , Z^9 and Z^{10} each independently represents an alkoxy group having 1 to 6 carbons; R^1 , R^2 , R^3 , R^4 , R^5 and R^6 each independently represents a monovalent hydrocarbon group which is optionally substituted; and R^7 , R^8 and R^9 each independently represents an alkyl group having 1 to 6 carbons.

wherein the composition comprises 10 ppm or less halogen impurity and 100 ppb or less metallic impurity wherein boron is counted in the metallic impurity.